

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	105	"438"/\$.ccls. and (Cu copper) same (trench via hole) same electrochemical adj deposition	USPAT	OR	ON	2005/11/28 12:31
L3	0	"438"/\$.ccls. and situ adj hydrogen adj plasma with remote adj hydrogen adj plasma with hydrogen adj plasma	USPAT	OR	ON	2005/11/28 12:32
L4	0	"438"/\$.ccls. and situ adj hydrogen adj plasma with remote adj hydrogen adj plasma	USPAT	OR	ON	2005/11/28 12:32
L5	0	situ adj hydrogen adj plasma with remote adj hydrogen adj plasma	USPAT	OR	ON	2005/11/28 12:33
L6	5	situ adj hydrogen adj plasma	USPAT	OR	ON	2005/11/28 12:35
L9	18	remote adj hydrogen adj plasma	USPAT	OR	ON	2005/11/28 12:57
L10	0	remote adj hydrogen adj plasma same in adj situ adj hydrogen adj plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 12:44
L11	0	remote adj hydrogen adj plasma same situ adj hydrogen adj plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 12:44
L12	1	remote adj hydrogen adj plasma and situ adj hydrogen adj plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 12:44
L13	3709	electrochemical adj process	USPAT	OR	ON	2005/11/28 12:57
L14	195	electrochemical adj process same reduc\$4 same oxidation	USPAT	OR	ON	2005/11/28 13:02